

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Young Hoon PARK, et al. )  
 ) Group Art Unit: 1763  
Serial No.: 10/511,883 )  
 )  
Filed: October 19, 2004 ) Examiner:  
 ) NG, James Wai Heung  
For: APPARATUS AND METHOD FOR )  
 )  
 ) DEPOSITING THIN FILM ON WAFER )  
 )  
 ) USING REMOTE PLASMA )

**REPLY TO NON-FINAL OFFICE ACTION  
UNDER 37 CFR 1.111, WITH AMENDMENT**

VIA EFS  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed January 10, 2008, Applicants request reconsideration in view of the following amendments and remarks for entry in the above-identified application.

**Amendments to the Claims** begin on page 2 of this paper; and

**Remarks** begin on page 8 of this paper.